Nikolai Salashchenko

List of Publications by Year in Descending Order

159 papers	1,237 citations	19 h-index	28 g-index
163 ext. papers	1,403 ext. citations	1 avg, IF	4.2 L-index

#	Paper	IF	Citations
159	Influence of ion-beam etching by Ar ions with an energy of 200-1000 eV on the roughness and sputtering yield of a single-crystal silicon surface.. *Applied Optics*, **2022**, 61, 2825-2833	1.7	0
158	KORTES Mission for Solar Activity Monitoring Onboard International Space Station. *Frontiers in Astronomy and Space Sciences*, **2021**, 8,	3.8	2
157	Emission Spectra of Light Inert Gases Ne and Ar in the 3–20 nm Range under Pulsed Laser Excitation Using Various Gas Jets as Targets. *Optics and Spectroscopy (English Translation of Optika I Spektroskopiya)*, **2021**, 129, 185-190	0.7	1
156	Emission Spectra of Heavy Inert Gases Kr and Xe in the Range from 3 to 20 nm Obtained under Pulsed Laser Excitation Using Various Gas Jets as Targets. *Optics and Spectroscopy (English Translation of Optika I Spektroskopiya)*, **2021**, 129, 363-368	0.7	
155	Emission Spectra of Molecular Gases N2 and CO2 in the Range of 3–20 nm upon Pulsed Laser Excitation of Various Gas-Jet Targets. *Optics and Spectroscopy (English Translation of Optika I Spektroskopiya)*, **2021**, 129, 789-793	0.7	
154	Y-Based Multilayer Mirrors for the Spectral Range of 8–12 nm. *Bulletin of the Lebedev Physics Institute*, **2021**, 48, 406-410	0.5	
153	High-resolution laboratory reflectometer for the study of x-ray optical elements in the soft and extreme ultraviolet wavelength ranges. *Review of Scientific Instruments*, **2020**, 91, 063103	1.7	2
152	Broadband Mirrors for Spectroheliographs at the KORTES Sun Study Facility. *Technical Physics*, **2020**, 65, 1792-1799	0.5	1
151	Application of Novel Multilayer Normal-Incidence Mirrors for EUV Solar Spectroscopy. *Technical Physics*, **2020**, 65, 1736-1739	0.5	1
150	The Smoothing Effect of Si Layers in Multilayer Be/Al Mirrors for the 17- to 31-nm Range. *Technical Physics*, **2020**, 65, 1786-1791	0.5	1
149	Multilayer Cr/Sc Mirrors with Improved Reflection for the "Water Transparency Window" Range. *Technical Physics*, **2020**, 65, 1809-1813	0.5	2
148	Obtaining of Smooth High-Precision Surfaces by the Mechanical Lapping Method. *Technical Physics*, **2020**, 65, 1873-1879	0.5	2
147	Reflecting properties of narrowband Si/Al/Sc multilayer mirrors at 58.4 nm. *Optics Letters*, **2020**, 45, 4666-4669	3	1
146	Optical constants of sputtered beryllium thin films determined from photoabsorption measurements in the spectral range 20.4-250 eV. *Journal of Synchrotron Radiation*, **2020**, 27, 75-82	2.4	2
145	Prospects for the Use of X-Ray Tubes with a Field-Emission Cathode and a Through-Type Anode in the Range of Soft X-Ray Radiation. *Technical Physics*, **2020**, 65, 1726-1735	0.5	1
144	The Microstructure of Transition Boundaries in Multilayer Mo/Be Systems. *Technical Physics*, **2020**, 65, 1800-1808	0.5	0
143	Ion-Beam Methods for High-Precision Processing of Optical Surfaces. *Technical Physics*, **2020**, 65, 1837-1845	0.5	0

142	Modification and Polishing of the Holographic Diffraction Grating Grooves by a Neutralized Ar Ion Beam. *Technical Physics*, **2020**, 65, 1780-1785	0.5	
141	Projection Objective For an EUV-Lithographic Workbench. *Journal of Surface Investigation*, **2020**, 14, 562-573	0.5	
140	Beryllium-Based Multilayer Mirrors for the Soft X-Ray and Extreme Ultraviolet Wavelength Ranges. *Journal of Surface Investigation*, **2020**, 14, 124-134	0.5	4
139	Mo/Si Multilayer Mirrors with B4C and Be Barrier Layers. *Journal of Surface Investigation*, **2019**, 13, 169-172	0.5	4
138	Aperiodic Mirrors Based on Multilayer Beryllium Systems. *Journal of Surface Investigation*, **2019**, 13, 267-271	0.5	2
137	Microstructure and Density of Mo Films in Multilayer Mo/Si Mirrors. *Journal of Surface Investigation*, **2019**, 13, 8-13	0.5	
136	Set of Multilayer X-Ray Mirrors for a Double-Mirror Monochromator Operating in the Wavelength Range of 0.41–5.5 nm. *Journal of Surface Investigation*, **2019**, 13, 1-7	0.5	4
135	Stable Multilayer Reflective Coatings for (HeI) = 58.4 nm for the KORTES Solar Telescope. *Technical Physics Letters*, **2019**, 45, 85-88	0.7	3
134	Multilayer X-Ray Image-Forming Optics. *Bulletin of the Russian Academy of Sciences: Physics*, **2019**, 83, 105-111	0.4	
133	X-ray scattering by the fused silica surface etched by low-energy Ar ions. *Journal of X-Ray Science and Technology*, **2019**, 27, 857-870	2.1	3
132	Observation of Laser-Induced Spark in the Density Jump in a Gas-Jet Target. *Technical Physics Letters*, **2019**, 45, 970-972	0.7	2
131	Optical, Mechanical, and Thermal Properties of Free-Standing MoSi2Nx and ZrSi2Ny Nanocomposite Films. *Technical Physics*, **2019**, 64, 1590-1595	0.5	0
130	Investigation of the thermo stability of aluminum thin-film filters with protective MoSi cap layers. *Applied Optics*, **2019**, 58, 21-28	1.7	2
129	Measurement Error of Interferometers with Diffraction Reference Wave. *Technical Physics*, **2019**, 64, 1698-1703	0.5	1
128	Influence of Thermal Annealing on the Properties of Multilayer Mo/Be Mirrors. *Technical Physics*, **2019**, 64, 1692-1697	0.5	2
127	Development of Technological Principles for Creating a System of Microfocus X-Ray Tubes Based on Silicon Field Emission Nanocathodes. *Technical Physics*, **2019**, 64, 1742-1748	0.5	3
126	Multilayer Ag/Y Mirrors for the Spectral Range of 9–11 nm. *Technical Physics*, **2019**, 64, 1684-1687	0.5	1
125	Beryllium as a Material for Thermally Stable X-Ray Mirrors. *Technical Physics*, **2019**, 64, 1596-1601	0.5	1

124	Fabrication and Study of a Concave Crystal Mirror for the KORTES Project. *Technical Physics*, **2019**, 64, 1680-1683	0.5	1
123	Influence of Beryllium Barrier Layers on the Properties of Mo/Si Multilayer Mirrors. *Technical Physics*, **2019**, 64, 1688-1691	0.5	2
122	Extending the Measurement Capabilities of a Model 130 Profilometer. *Journal of Surface Investigation*, **2019**, 13, 889-893	0.5	
121	Modular Device for the Formation and Study of Cluster Beams of Inert and Molecular Gases. *Journal of Surface Investigation*, **2019**, 13, 862-869	0.5	1
120	Emission Properties of Laser Plasma Excited on Molecular-Cluster Carbon Dioxide Jets. *Technical Physics*, **2019**, 64, 1566-1572	0.5	
119	Optimization of Composition, Synthesis, and Study of Broadband Multilayer Mirrors for the EUV Spectral Range. *Technical Physics*, **2019**, 64, 1673-1679	0.5	1
118	Study of oxidation processes in Mo/Be multilayers. *AIP Advances*, **2018**, 8, 075202	1.5	12
117	Influence of barrier interlayers on the performance of Mo/Be multilayer mirrors for next-generation EUV lithography. *Optics Express*, **2018**, 26, 33718-33731	3.3	18
116	Current State of Development of a Microscope Operating at a Wavelength of 3.37 nm at the Institute of Physics of Microstructures of the Russian Academy of Sciences. *Journal of Surface Investigation*, **2018**, 12, 1253-1263	0.5	4
115	Electron Energy Conversion to EUV Radiation in the K□Line of Be in the □Shooting Through□ Geometry. *Journal of Experimental and Theoretical Physics*, **2018**, 127, 985-993	1	3
114	Conversion efficiency of a laser-plasma source based on a Xe jet in the vicinity of a wavelength of 11 nm. *AIP Advances*, **2018**, 8, 105003	1.5	14
113	Observation of extreme ultraviolet light emission from an expanding plasma jet with multiply charged argon or xenon ions. *Applied Physics Letters*, **2018**, 113, 153502	3.4	15
112	Maskless X-Ray Lithography Based on Microoptical Electromechanical Systems and Microfocus X-Ray Tubes. *Journal of Surface Investigation*, **2018**, 12, 944-952	0.5	5
111	Microfocus X-Ray Tubes with a Silicon Autoemission Nanocathode as an X-Ray Source. *Bulletin of the Lebedev Physics Institute*, **2018**, 45, 1-5	0.5	5
110	A double-stream Xe:He jet plasma emission in the vicinity of 6.7 nm. *Applied Physics Letters*, **2018**, 112, 221101	3.4	11
109	Effect of structural defects of aperiodic multilayer mirrors on the properties of reflected (sub)femtosecond pulses. *Quantum Electronics*, **2017**, 47, 378-384	1.8	8
108	Laboratory reflectometer for the investigation of optical elements in a wavelength range of 5 □50 nm: description and testing results. *Quantum Electronics*, **2017**, 47, 385-392	1.8	16
107	Current status and development prospects for multilayer X-ray optics at the Institute for Physics of Microstructures, Russian Academy of Sciences. *Journal of Surface Investigation*, **2017**, 11, 1-19	0.5	21

106	Deposition of Mo/Si multilayers onto MEMS micromirrors and its utilization for extreme ultraviolet maskless lithography. *Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics*, **2017**, 35, 062002	1.3	10
105	Extended model for the reconstruction of periodic multilayers from extreme ultraviolet and X-ray reflectivity data. *Journal of Applied Crystallography*, **2017**, 50, 1428-1440	3.8	31
104	Deformation-free rim for the primary mirror of telescope having sub-second resolution **2017**,		3
103	Application of cluster beams for the physics and technologies of microstructures. *Journal of Surface Investigation*, **2017**, 11, 496-500	0.5	6
102	The effect of bombardment with neutralized neon ions on the roughness of a fused silica and beryllium surface. *Journal of Surface Investigation*, **2017**, 11, 485-489	0.5	1
101	Surface shape measurement of mirrors in the form of rotation figures by using point diffraction interferometer. *Journal of Modern Optics*, **2017**, 64, 413-421	1.1	3
100	Thin film multilayer filters for solar EUV telescopes. *Applied Optics*, **2016**, 55, 4683-90	0.2	19
99	Ion-beam polishing of fused silica substrates for imaging soft x-ray and extreme ultraviolet optics. *Applied Optics*, **2016**, 55, 1249-56	0.2	39
98	Problems in the application of a null lens for precise measurements of aspheric mirrors. *Applied Optics*, **2016**, 55, 619-25	0.2	29
97	Advanced materials for multilayer mirrors for extreme ultraviolet solar astronomy. *Applied Optics*, **2016**, 55, 2126-35	0.2	41
96	Problems and prospects of maskless (B)EUV lithography **2016**,		2
95	The diffraction efficiency of echelle gratings increased by ion-beam polishing of groove surfaces. *Technical Physics Letters*, **2016**, 42, 844-847	0.7	7
94	X-ray optical system for imaging laser plumes with a spatial resolution of up to 70 nm. *Quantum Electronics*, **2016**, 46, 347-352	1.8	2
93	Reflective Schmidt-Cassegrain system for large-aperture telescopes. *Applied Optics*, **2016**, 55, 4430-5	0.2	11
92	Effect of roughness, deterministic and random errors in film thickness on the reflecting properties of aperiodic mirrors for the EUV range. *Quantum Electronics*, **2016**, 46, 406-413	1.8	5
91	Note: A stand on the basis of atomic force microscope to study substrates for imaging optics. *Review of Scientific Instruments*, **2015**, 86, 016102	1.7	25
90	Sub-micrometer resolution proximity X-ray microscope with digital image registration. *Review of Scientific Instruments*, **2015**, 86, 063701	1.7	5
89	Resolving capacity of the circular Zernike polynomials. *Optics Express*, **2015**, 23, 14677-94	3.3	22

88	Application of point diffraction interferometry for middle spatial frequency roughness detection. *Optics Letters*, **2015**, 40, 159-62	3	14
87	Design of a soft X-ray and extreme UV reflectometer equipped with a high-resolution monochromator and high-brightness laser-plasma radiation source. *Journal of Surface Investigation*, **2015**, 9, 726-734	0.5	4
86	Preparation and roughness metrology of supersmooth optical surfaces. *Journal of Surface Investigation*, **2015**, 9, 761-764	0.5	8
85	Precision aspherization of the surface of optical elements by ion-beam etching. *Journal of Surface Investigation*, **2015**, 9, 765-770	0.5	8
84	Application of point diffraction interferometry for measuring angular displacement to a sensitivity of 0.01 arcsec. *Applied Optics*, **2015**, 54, 9315-9	0.2	2
83	A Two-coordinate digital detector for microscopy in the soft X-ray region. *Bulletin of the Russian Academy of Sciences: Physics*, **2014**, 78, 64-67	0.4	
82	Using Ion-beam etching to smooth fused silica surfaces. *Bulletin of the Russian Academy of Sciences: Physics*, **2014**, 78, 57-60	0.4	2
81	High performance multilayer La/B4C mirrors with carbon barrier layers. *Bulletin of the Russian Academy of Sciences: Physics*, **2014**, 78, 61-63	0.4	3
80	Effect of polymer matrix and photoacid generator on the lithographic properties of chemically amplified photoresist. *Russian Microelectronics*, **2014**, 43, 392-400	0.5	3
79	Roughness measurement and ion-beam polishing of super-smooth optical surfaces of fused quartz and optical ceramics. *Optics Express*, **2014**, 22, 20094-106	3.3	48
78	Nanostructure formation on an EUV lithographer stand: First results. *Bulletin of the Russian Academy of Sciences: Physics*, **2013**, 77, 1-5	0.4	1
77	A laser plasma source of EUV radiation for projection nanolithography. *Bulletin of the Russian Academy of Sciences: Physics*, **2013**, 77, 6-9	0.4	2
76	Multilayer La/B4C mirrors in the spectral region near 6.7 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2013**, 77, 24-27	0.4	2
75	Comparative heat load testing of freestanding multilayer Mo/ZrSi2 and Mo/NbSi2. *Bulletin of the Russian Academy of Sciences: Physics*, **2013**, 77, 83-85	0.4	
74	Next generation nanolithography based on Ru/Be and Rh/Sr multilayer optics. *AIP Advances*, **2013**, 3, 082130	1.5	44
73	Chemically amplified resists for high-resolution lithography. *Russian Microelectronics*, **2013**, 42, 165-175	0.5	6
72	Multilayer X-ray mirrors for the (4.48)-nm carbon-window spectral region. *Crystallography Reports*, **2013**, 58, 505-508	0.6	3
71	Polished sitall substrates for X-ray optics. *Journal of Surface Investigation*, **2013**, 7, 612-616	0.5	6

70	Apparatus for the magnetron and ion-beam synthesis of multilayer structures. *Journal of Surface Investigation*, **2013**, 7, 637-639	0.5	5
69	Investigation of supersmooth optical surfaces and multilayer elements using soft X-ray radiation. *Technical Physics*, **2013**, 58, 1371-1379	0.5	7
68	On the problems of the application of atomic-force microscopes for studying the surface roughness of elements for imaging optics. *Journal of Surface Investigation*, **2013**, 7, 797-801	0.5	4
67	Device for the precise shape correction of optical surfaces by ion-beam and reactive plasma etching. *Journal of Surface Investigation*, **2013**, 7, 913-915	0.5	11
66	High performance La/B4C multilayer mirrors with barrier layers for the next generation lithography. *Applied Physics Letters*, **2013**, 102, 011602	3.4	38
65	Carbon K-edge polarimetry with Cr/Sc multilayers. *Journal of Physics: Conference Series*, **2013**, 425, 122013	0.3	14
64	Mirrors with a Subnanometer Surface Shape Accuracy **2013**, 595-616		1
63	The evolution of roughness of supersmooth surfaces by ion-beam etching. *Bulletin of the Russian Academy of Sciences: Physics*, **2012**, 76, 163-167	0.4	17
62	Influence of the chemical structure of (co)polymer resists on their sensitivity to radiation. *Bulletin of the Russian Academy of Sciences: Physics*, **2012**, 76, 159-162	0.4	3
61	Possibility for the form correction of X-ray mirrors by reactive ion-beam etching. *Journal of Surface Investigation*, **2012**, 6, 487-489	0.5	3
60	Thermal stability of a freestanding EUV filter under long-term vacuum annealing at 700–1000°C. *Journal of Surface Investigation*, **2012**, 6, 482-486	0.5	2
59	Diffraction-limited short-wavelength optics: Analysis, fabrication, and application. *Journal of Surface Investigation*, **2012**, 6, 464-472	0.5	1
58	Reflective mask for projection lithography operating at a wavelength of 13.5 nm. *Journal of Surface Investigation*, **2012**, 6, 568-573	0.5	3
57	Applying reactive ionic-beam etching to correcting the shape of X-ray mirrors. *Bulletin of the Russian Academy of Sciences: Physics*, **2012**, 76, 168-170	0.4	4
56	Problem of roughness detection for supersmooth surfaces **2011**,		7
55	Manufacturing and characterization of diffraction quality normal incidence optics for the XEUV range **2011**,		4
54	Freestanding multilayer films for application as phase retarders and spectral purity filters in the soft x-ray and EUV ranges **2011**,		2
53	Measurement of the profile and curvature of cylindrical multilayer mirrors irradiated by a divergent X-ray beam. *Journal of Surface Investigation*, **2011**, 5, 526-528	0.5	1

52	Design of the aspheric Schwarzschild lens for a nanolithographer with the operating wavelength = 13.5 nm. *Journal of Surface Investigation*, **2011**, 5, 512-516	0.5	
51	System for illumination of an EUV-nanolithograph mask. *Journal of Surface Investigation*, **2011**, 5, 517-519	0.5	3
50	Particulars of studying the roughness of substrates for multilayer X-ray optics using small-angle X-ray reflectometry, atomic-force, and interference microscopy. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 67-72	0.4	22
49	Mo-based EUV multilayer filters with enhanced thermal stability. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 73-75	0.4	2
48	Evolution of elemental distribution in free-standing structures of Zr/ZrSi2 with MoSi2 and ZrSi2 protective coatings under annealing. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 76-79	0.4	2
47	Choosing optical materials for diagnostics of the solar atmosphere in the wavelength range of 60 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 84-86	0.4	4
46	Project for manufacturing a Russian EUV nanolithographer for the fabrication of chips according to technological standards of 22 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 44-48	0.4	
45	Evolution of the roughness of amorphous quartz surfaces and Cr/Sc multilayer structures upon exposure to ion-beam etching. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 61-63	0.4	10
44	An extreme ultraviolet radiation source based on plasma heated by millimeter range radiation. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 64-66	0.4	5
43	A stand for a projection EUV nanolithographer-multiplicator with a design resolution of 30 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 49-52	0.4	14
42	A technological complex for manufacturing of precise imaging optics. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 53-56	0.4	3
41	Two-mirror projection objective of a nanolithographer at 13.5 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 57-60	0.4	5
40	Details of how to mount high-precision optics. *Journal of Surface Investigation*, **2010**, 4, 359-365	0.5	2
39	SIMS study of annealing effect on element distribution in free-standing Al/Si and Zr/ZrSi2 multilayer films. *Journal of Surface Investigation*, **2010**, 4, 405-410	0.5	1
38	New focusing multilayer structures for X-ray and VUV plasma spectroscopy. *Technical Physics*, **2010**, 55, 1018-1023	0.5	3
37	Multilayer X-ray mirrors based on La/B4C and La/B9C. *Technical Physics*, **2010**, 55, 1168-1174	0.5	26
36	On creating multilayer X-ray focusing mirrors. *Bulletin of the Russian Academy of Sciences: Physics*, **2010**, 74, 38-40	0.4	1
35	Multilayer thin-film filters of extreme ultraviolet and soft X-ray spectral regions. *Bulletin of the Russian Academy of Sciences: Physics*, **2010**, 74, 46-49	0.4	7

34	Componentry of reflection optics for application in the tesis X-ray astrophysics experiment. *Bulletin of the Russian Academy of Sciences: Physics*, **2010**, 74, 50-52	0.4	10
33	Physical limitations of measurement accuracy of the diffraction reference wave interferometers. *Bulletin of the Russian Academy of Sciences: Physics*, **2010**, 74, 53-56	0.4	10
32	10.1007/s11448-008-1007-7 **2010**, 87, 27		
31	Influence of annealing on the structural and optical properties of thin multilayer EUV filters containing Zr, Mo, and silicides of these metals **2009**,		9
30	Activity in manufacturing and characterization of X-ray optical elements and ultrahigh-resolution systems at IPM RAS. *Bulletin of the Russian Academy of Sciences: Physics*, **2009**, 73, 62-65	0.4	
29	X-ray and vacuum-ultraviolet plasma spectroscopy with the use of new focusing multilayer structures. *JETP Letters*, **2008**, 87, 27-29	1.2	3
28	Extreme-ultraviolet source based on the electron-cyclotron-resonance discharge. *JETP Letters*, **2008**, 88, 95-98	1.2	11
27	New focusing multilayer structures for X-ray plasma spectroscopy. *Quantum Electronics*, **2008**, 38, 169-171	1.8	3
26	A source of a reference spherical wave based on a single mode optical fiber with a narrowed exit aperture. *Review of Scientific Instruments*, **2008**, 79, 033107	1.7	34
25	Multilayer Zr/Si filters for EUV lithography and for radiation source metrology **2008**,		25
24	Testing and correction of optical elements with subnanometer precision. *Nanotechnologies in Russia*, **2008**, 3, 602-610	0.6	12
23	Shortwave projection nanolithography. *Herald of the Russian Academy of Sciences*, **2008**, 78, 279-285	0.7	10
22	Effect of pinhole roughness on light diffraction. *Journal of Surface Investigation*, **2008**, 2, 511-513	0.5	1
21	X-ray intensity distribution in the image plane of elliptic multilayer mirrors. *Journal of Surface Investigation*, **2007**, 1, 235-239	0.5	1
20	A multilayer x-ray mirror in the form of an ellipsoid of revolution. *Bulletin of the Russian Academy of Sciences: Physics*, **2007**, 71, 64-67	0.4	2
19	Multilayer x-ray mirrors based on W/B 4 C with ultrashort (d = 0.7–1.5 nm) periods. *Journal of Surface Investigation*, **2007**, 1, 7-12	0.5	1
18	Analysis of cross-correlation of interface roughness in multilayer structures with ultrashort periods. *Journal of Experimental and Theoretical Physics*, **2006**, 103, 346-353	1	7
17	Multilayer mirror systems to form hard X-ray beams. *Open Physics*, **2005**, 3,	1.3	6

16	Short-period multilayer X-ray mirrors. *Journal of Synchrotron Radiation*, **2003**, 10, 358-60	2.4	19
15	Interface Sensitive Investigation of 57Fe/Cr Superstructure by Means of Nuclear Resonance Standing Waves in Time Scale. *Hyperfine Interactions*, **2002**, 141/142, 119-123	0.8	4
14	Observation of laser-induced local modification of magnetic order in transition metal layers. *JETP Letters*, **2001**, 73, 192-196	1.2	7
13	Novel instrumentation for spectrally resolved soft x-ray plasma tomography: Development and pilot results on TEXTOR. *Review of Scientific Instruments*, **2001**, 72, 1411	1.7	8
12	Magnetic nanodot arrays produced by direct laser interference lithography. *Applied Physics Letters*, **2001**, 79, 2606-2608	3.4	67
11	Cr /sc multilayers for the soft-x-ray range. *Applied Optics*, **1998**, 37, 719-28	1.7	51
10	Fatigue in epitaxial lead zirconate titanate films. *Physics of the Solid State*, **1997**, 39, 609-610	0.8	3
9	Resonance enhancement of diffuse scattering of x-rays in a waveguide heterostructure. *JETP Letters*, **1997**, 66, 236-240	1.2	1
8	Magnetic ordering in Fe-containing spinodally decomposing materials synthesized from laser plasma. *Physical Review B*, **1995**, 52, 10303-10314	3.3	9
7	Fabrication and investigation of imaging normal-incidence multilayer mirrors with a narrow-band reflection in the range simeq 4.5 nm. *Physica Scripta*, **1993**, 48, 516-520	2.6	12
6	Resonant diffraction of synchrotron radiation by a nuclear multilayer. *Physical Review Letters*, **1993**, 71, 2489-2492	7.4	55
5	Absolute radiometry technique for VUV and SXR radiation fluxes. *Zeitschrift F Physik D-Atoms Molecules and Clusters*, **1991**, 21, S161-S162		1
4	Absolute photometry of pulsed intense fluxes of ultrasoft X-ray radiation. *Physica Scripta*, **1991**, 43, 356-367	2.6	16
3	Normal-incidence multilayer mirrors for the 120-450 wavelength region. *Journal of X-Ray Science and Technology*, **1990**, 2, 241-8	2.1	
2	Multilayer Dispersion Elements For X-Ray Emission At = 17 - 100 **1985**, 0473, 298		
1	The possibility of using a laser to obtain ultrathin continuous single-crystal films. *Radiophysics and Quantum Electronics*, **1975**, 18, 674-675	0.7	